

3720 U.S. PTO
10/024958
12/18/01

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10024958	FILING DATE 12/18/2001	CLASS 430216	SUBCLASS 53	GAU 1758	EXAMINER Chen
**APPLICANTS: Buie Melisa; Stoehr Brigitte; Ruhl Guenther;					
**CONTINUING DATA VERIFIED: THIS APPLICATION IS A CIP OF PCT/US01/19292 06/15/2001					
** FOREIGN APPLICATIONS VERIFIED: GERMANY 101 46 935.7 09/24/2001					
PG-PUB		DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>	
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO AMA/4213.P1/ETCH/METAL/JB	
TITLE : Etch process for photolithographic reticle manufacturing with improved etch bias <small>U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)</small>					

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
Assistant Examiner		DRAWING	
		Sheets Drwg.	Figs. Drwg.
ISSUE FEE Amount Due Date Paid		Print Fig.	
<input type="checkbox"/> TERMINAL DISCLAIMER		Primary Examiner Prepared for Issue Application Examiner	
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